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8. **(Twice Amended)** The pellicle of Claim 7, wherein maximizing transmission of the exposure wavelength at the angle of incidence greater than zero comprises increasing the optical thickness over a design thickness by less than or equal to approximately one-quarter of the exposure wavelength.

9. **(Twice Amended)** The pellicle of Claim 7, further comprising the peak in transmission located between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

10. The pellicle of Claim 7, further comprising an anti-reflective coating disposed on a top surface and a bottom surface of the thin film.

11. The pellicle of Claim 10, wherein the anti-reflective coating includes a first refractive index approximately equal to the square root of a second refractive index associated with the thin film.

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12. **(Twice Amended)** The pellicle of Claim 10, further comprising the peak in transmission located between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

13. The pellicle of Claim 10, wherein the anti-reflective coating includes a thickness between approximately one-quarter of the exposure wavelength and approximately one-half of the exposure wavelength.

14. The pellicle of Claim 7, further comprising a plurality of adjoining anti-reflective coatings disposed on a top surface and a bottom surface of the thin film, each of the anti-reflective coatings including a different refractive index.

15. The pellicle of Claim 7, wherein the thin film comprises an amorphous fluoropolymer.

16. The pellicle of Claim 7, wherein:  
the thin film includes a thickness of approximately 855 nanometers; and  
the exposure wavelength is between approximately 248 nanometers and  
approximately 436 nanometers.

17. **(Twice Amended)** A photolithography system for optimizing off-axis  
transmission of light, comprising:  
a photomask; and  
a pellicle comprising:  
a frame coupled to the photomask; and  
a thin film operable to transmit approximately ninety-nine percent (99%) of  
off-axis light at an exposure wavelength, the thin film including an optical thickness that  
produces a peak in transmission for normal incidence light at a wavelength greater than the  
exposure wavelength.

18. **(Twice Amended)** The system of Claim 17, wherein transmitting  
approximately 99% of the off-axis light at the exposure wavelength comprises increasing the  
optical thickness over a design thickness by less than or equal to approximately one-quarter  
of the exposure wavelength.

19. **(Twice Amended)** The system of Claim 17, further comprising the peak in  
transmission located between approximately one nanometer and approximately twenty  
nanometers above the exposure wavelength.

20. The system of Claim 17, further comprising an anti-reflective coating disposed  
on a top surface and a bottom surface of the thin film, the anti-reflective coating including a  
thickness between approximately one-quarter of the exposure wavelength and approximately  
one-half of the exposure wavelength.

B5 21. **(Twice Amended)** The system of Claim 20, further comprising the peak in transmission located between approximately one nanometer and approximately twenty nanometers above the exposure wavelength.

22. The system of Claim 20, wherein the anti-reflective coating includes a first refractive index approximately equal to the square root of a second refractive index associated with the thin film.

23. The system of Claim 17, further comprising a plurality of adjoining anti-reflective coatings disposed on a top surface and a bottom surface of the thin film, each of the anti-reflective coatings including a different refractive index.

24. The system of Claim 17, wherein the frame comprises aluminum.

25. The system of Claim 17, wherein the thin film comprises an amorphous fluoropolymer.

B6 26. **(Twice Amended)** A method for performing photolithography, comprising:  
forming a thin film including an optical thickness, the optical thickness operable to produce a peak in transmission for normal incidence light at a wavelength greater than an exposure wavelength and maximize transmission of the exposure wavelength at an angle of incidence greater than zero;

attaching the thin film to a frame to form a pellicle;  
mounting the pellicle to a photomask; and  
exposing the pellicle and the photomask to radiant energy having the exposure wavelength.

27. The method of Claim 26, further comprising coating a top surface of the thin film with an anti-reflective material, the anti-reflective material including a thickness between approximately one-quarter of the exposure wavelength and approximately one-half of the exposure wavelength.